

Synthesis of Functional Ceramic Materials through Controlling Thermal Plasma Chemical Reactions

Plasma Processing Group

Nano Ceramics Center

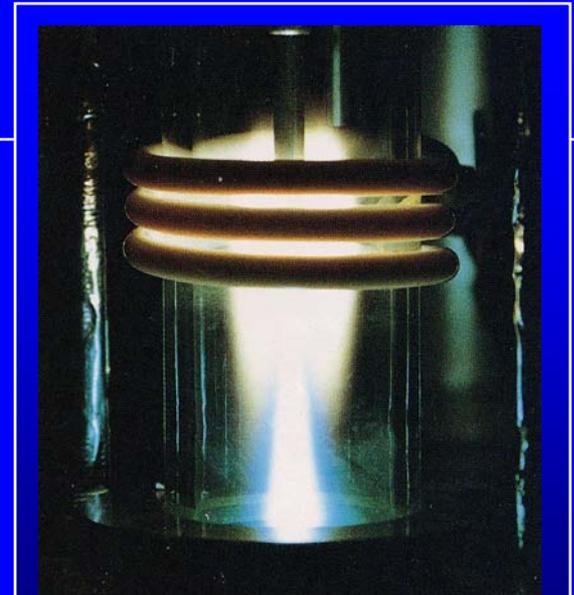
National Institute for Materials Science

We are trying to utilize **chemical aspect** of thermal plasma, which has been used mostly for **high-temperature heat source**.

- ✓ New generation method; **time-domain control**.
- ✓ New chemical reaction field.

Characteristics of thermal plasma

1. High temperature; 10,000-15,000K.
2. Generation at relatively high pressure; ~ 1 atom.
Equilibrated plasma; $T_e/T_g \sim 1$.
High concentration of chemically reactive species.
3. Very rapid cooling in the plasma tail, 10^{4-6} K/s.
4. Discharge without a electrode; oxidative, reductive, and reactive plasmas can be generated.



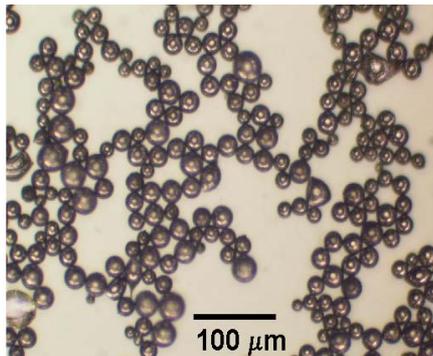
Generation of Induction Thermal Plasma

Thermal plasma gives unique reaction fields for materials processing.

High temperature
heat source

Chemical reaction
fields

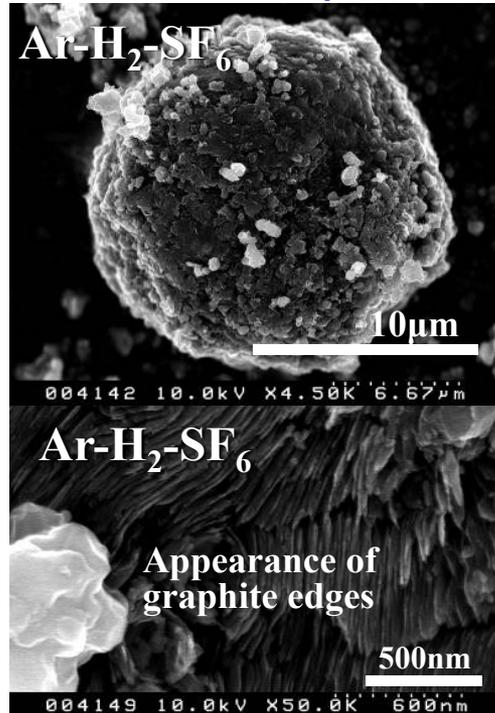
Much heat transfer
from plasma to particles.
Spheroidization in thermal plasma



Refractory TiC particles were melted and spheroidized in thermal plasma.
[*J. Am. Ceram. Soc.*, 84, 1929(2001).]

For example, 30 kg/h (1 ton/week) of tungsten powders can be spheroidized.

Graphite powder treatment in
reactive thermal plasma

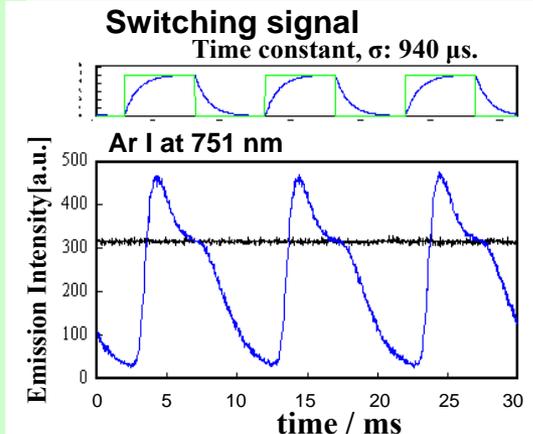


Disordering of graphite structure and the introduction of functional groups at surface.

Improvement of charge-discharge characteristics of lithium-ion rechargeable battery.

[*Carbon*, 42, 3229(2004).]

New plasma generation method
Pulse-Modulated RF Induction Plasma -



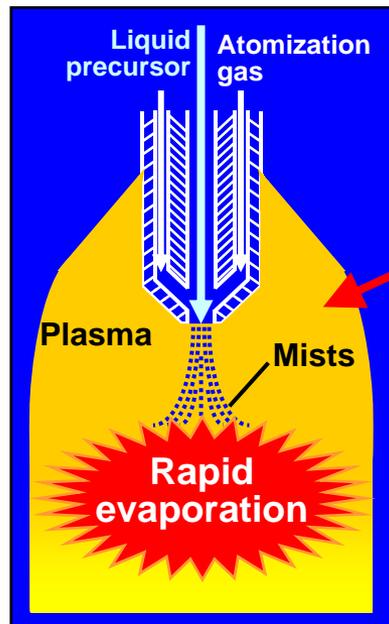
Response of plasma emission to the switching signal.

Improvement of UV emission of ZnO by hydrogen doping.

[*Appl. Phys. Lett.*, 71, 3787(1997);
ibid., 80, 2869(2002).]

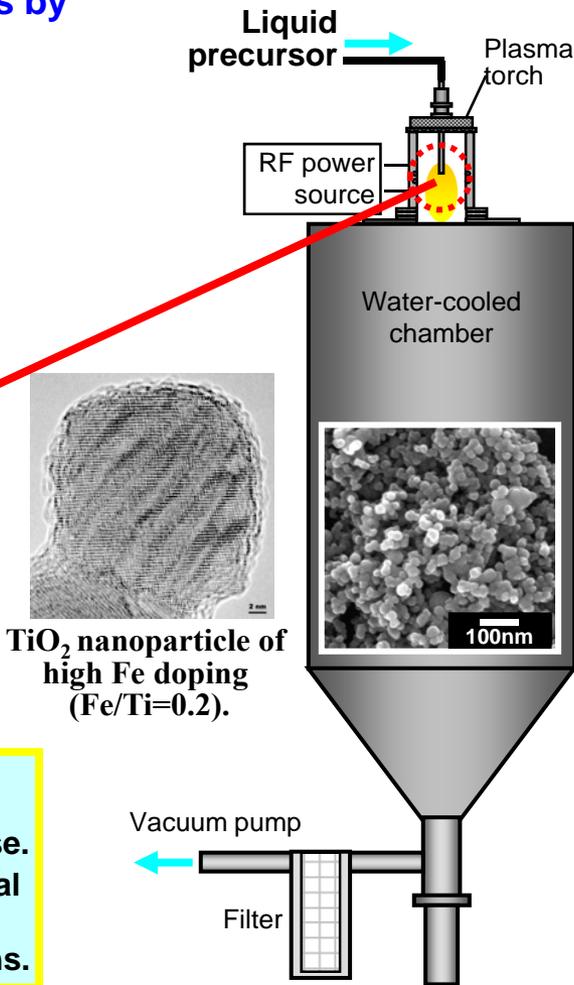
Synthesis of functional ceramic nanoparticles through controlled reactive thermal plasma processing

Synthesis of nanoparticles by plasma oxidation of liquid precursor mists

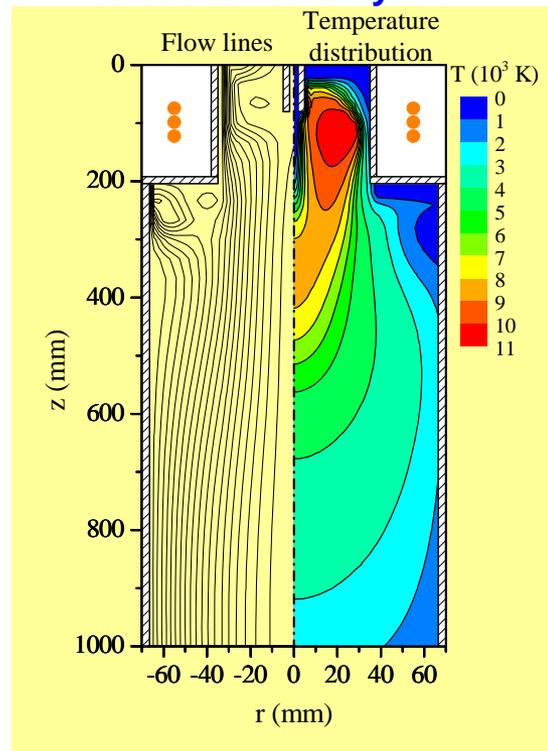


Advantages

- // High degree of supersaturation in a vapor phase.
- // Precise control of chemical composition.
- // Non-equilibrium conditions.



Optimization of reactor design and process parameters by numerical analysis



- // Rapid quenching condition, and the flat radial distributions of flow and temperature.

- // Particle size control, and sharp size distribution.